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ABSTRACT

0045 A back-end method for photomask making generally includes the steps of inspecting a photomask and repairing each defect on the photomask. The step of inspecting the photomask preferably comprises a defect finder mark implementation routine. In general, when inspecting the photomask for defects, the defect finder mark implementation routine deposits a defect finder mark on the photomask via a mark installer (not shown) included with a mask marking inspection system. Deposition of the defect finder mark includes establishing a location that is adjacent to the defect and establishing a size that is detectable by a mask repair device (not shown). By deposition on the photomask, the defect finder mark reliably facilitates location of the corresponding defect despite variations in image resolution and stage movement between the mask marking inspection system and the mask repair device.